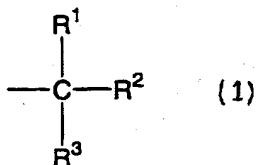


Abstract

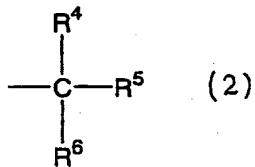
The present invention relates to a positive-working radiation-sensitive composition which is characterized in 5 that it contains a compound meeting any of conditions a1) to a3), and b) an acid generator which generates acid by irradiation with radiation; and also to a method for the production of a resist pattern employing same.

10 a1) A compound wherein a carboxyl group is protected by an acid labile group represented by general formula (1)



(R^1 and R^2 are aromatic rings, and R^3 represents an alkyl group, a substituted alkyl group, a cycloalkyl group or an 15 aromatic ring. R^1 to R^3 may be the same or different.)

a2) A compound in which an alkali-soluble group is protected by an acid labile group represented by general formula (2)



20 (R^4 to R^6 are each an alkyl group, a substituted alkyl group, a cycloalkyl group or an aromatic ring, and at least one of R^4 to R^6 is an aromatic ring with an electron-donating group. R^4 to R^6 may be the same or different.)

25 a3) A compound in which an alkali-soluble group is protected by an acid labile group a, and either acid labile group a has